



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION  
METROLOGY SYSTEM  
INTEGRATED INTO  
SEMICONDUCTOR WAFER  
PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO OFFICE ACTION  
MAILED NOVEMBER 10, 2005**

353 Sacramento St., Suite 2200  
San Francisco, CA 94111  
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M/S AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited  
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envelope, addressed to: Commissioner for Patents, P.O.  
Box 1450, Alexandria, VA 22313-1450 on April 4, 2006.

STALLMAN &amp; POLLOCK LLP

Dated: 04/04/2006

By: 

Lana T. Brenner

Sir:

In response to the Office Action mailed November 10, 2005, please amend the above-  
identified application as follows:

**Amendments to the Claims** are reflected in the Listing of Claims that begins on page 2 of this  
paper.

**Remarks** begin on page 7 of this paper.

04/07/2006 SDENBOB1 00000038 09927102

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